

IN THE SPECIFICATION

Please amend the paragraph at page 7, lines 4-12, as follows:

~~Because, the~~ The amorphous silicon has a ~~erystalline~~ structure having a high degree of freedom such that it is easily fused under an atmosphere of a high temperature as in the regeneration of the filter and is easily back to the original amorphous silicon as in the completion of the regeneration. Therefore, it is considered that when the thermal stress is applied, even if fine cracks are created between ceramic particles, the growth of the cracks can be prevented by again bonding the particles between silicon.